U_{1.33}T₄Al₈Si₂ (T = Ni, Co): Complex uranium silicides grown from aluminum/gallium flux mixtures

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Supporting Information

Figure S1. Microscope images of flux-grown uranium silicides. (a) Pencil-shaped $U_{1.33}Co_4Al_8Si_2$ crystals. (b) $U(Al/Ga/Si)_3$ crystals that form as a byproduct in reactions of U/Ni/Si in Ga/Al flux.

Figure S2. X-ray powder diffraction pattern for products of the reaction of U/Ni/Si in Al/Ga flux (bottom), compared to calculated patterns for $U_{1.33}Ni_4Al_8Si_2$ and $U(Al/Si)_3$.

Figure S3. X-ray powder diffraction pattern for products of the reaction of U/Co/Si in Al/Ga flux, compared to calculated pattern for $U_{1.33}Co_4Al_8Si_2$.

Figure S4. EDS mapping of $U_{1.33}Ni_4Al_8Si_2$ crystal after TGA experiment (heated to 900°C in flowing air).

Figure S5. Thermogravimetric analysis of $U_{1.33}Co_4Al_8Si_2$ crystals heated in air, and microscope image of oxide coated crystals.

Table S1. Selected bond lengths (in Å) in the $U_{1.33}T_4Al_8Si_2$ structures (T = Ni or Co).

Table S2. Atomic percentages based on single crystal X-ray diffraction and SEM EDS for $U_{1.33}Ni_4Al_8Si_2$ compound.

Table S3. Atomic percentages based on single crystal X-ray diffraction and SEM EDS for $U_{1.33}Co_4Al_8Si_2$ compound.

Table S4. Atomic coordinates and site occupancies for U_{1.33}Ni₄Al₈Si₂ structure.

Table S5. Atomic coordinates and site occupancies for $U_{1.33}Co_4Al_8Si_2$ structure.



Figure S1. Microscope images of flux-grown uranium silicides. (a) Pencil-shaped $U_{1.33}Co_4Al_8Si_2$ crystals. (b) U(Al/Ga/Si)₃ crystals that form as a byproduct in reactions of U/Ni/Si in Ga/Al flux.



Figure S2. X-ray powder diffraction pattern for products of the reaction of U/Ni/Si in Al/Ga flux (bottom), compared to calculated patterns for $U_{1.33}Ni_4Al_8Si_2$ and $U(Al/Si)_3$.



Figure S3. X-ray powder diffraction pattern for products of the reaction of U/Co/Si in Al/Ga flux, compared to calculated pattern for $U_{1.33}Co_4Al_8Si_2$.



Figure S4. EDS mapping of $U_{1.33}Ni_4Al_8Si_2$ crystal after TGA experiment (heated to 900°C in flowing air).



Figure S5. Thermogravimetric analysis of $U_{1.33}Co_4Al_8Si_2$ crystals heated in air, and microscope image of oxide coated crystals.

	U1.33Ni4Al8Si2	U1.33C04Al8Si2
U(1)-Si(1)	2.986(5)	2.900(3)
U(1)-Al(1)	3.0036(13)	2.9819(9)
T(1)-Si(1)	2.397(3)	2.3140(17)
T(1)-Al(1)	2.4087(5)	2.3534(4)
T(1)-Al(2)	2.479(3)	2.5721(8)
Al(1)-Al(2)	2.7451(15)	2.6991(12)
Al(1)-Si(1)	2.7665(14)	2.7557(10)
Si(1)-Si(1)	2.448(11)	2.474(6)

Table S1. Selected bond lengths (in Å) in the $U_{1.33}T_4Al_8Si_2$ structures (T = Ni or Co).

	Atomic percentages based on single crystal formula (%)	Atomic percentages based on SEM/EDS (%)
U	7	7(1)
Ni	27	31(4)
Al	51	41(4)
Si	12	16(2)
Ga	3	5(1)

Table S2. Atomic percentages based on single crystal X-ray diffraction and SEM EDS for $U_{1.33}Ni_4Al_8Si_2$ compound.

Table S3. Atomic percentages based on single crystal X-ray diffraction and SEM EDS for $U_{1.33}Co_4Al_8Si_2$ compound.

	Atomic percentages based on single crystal formula (%)	Atomic percentages based on SEM/EDS (%)
U	9	10(1)
Co	26	25(5)
Al	51	39(4)
Si	13	19(3)
Ga	1	7(2)

Table S4. Atomic coordinates and site occupancies for U_{1.33}Ni₄Al₈Si₂ structure.

Atom	Site	X	У	Z	Occupancy
U1	2(c)	1/3	2/3	1/4	0.526
Ni1	4(f)	1/3	2/3	0.61067(6)	1
Al1	4(e)	0	0	0.1337(1)	0.928
Ga11	4(e)	0	0	0.1337(1)	0.072
A12	4(f)	1/3	2/3	0.0469(1)	1
Si1	6(h)	0.5311(9)	0.062(2)	1/4	0.300
Ga1	6(h)	0.5311(9)	0.062(2)	1/4	0.033

Table S5. Atomic coordinates and site occupancies for U_{1.33}Co₄Al₈Si₂ structure.

Atom	Site	Х	У	Z	Occupancy
U1	2(c)	1/3	2/3	1/4	0.679
Co1	4(f)	1/3	2/3	0.61412(6)	1
Al1	4(e)	0	0	0.1318(1)	0.946
Ga1	4(e)	0	0	0.1318(1)	0.054
A12	4(f)	1/3	2/3	0.0455(1)	1
Si1	6(h)	0.5367(5)	0.073(1)	1/4	0.322